FUJI SUPER MICRO PHOTOPLATE HM-G

FEATURES AND APPLICATIONS

Fuji Super Micro Photoplate HM-G is a high-resolution glass plate designed to obtain high-density practical patterns and fine line width reproducibility. It is suitable for creating a high-precision master photomask in photoplotter drawings and a working photomask in contact work.

- HM-G has sensitivity suitable for photoplotters to provide extremely high-resolution, sharp edged images.
- HM-G has wide exposure latitude and development latitude, allowing highly accurate line width reproduction.
- HM-G's superior latent image stability makes it possible to create a photomask with good image precision.

TYPE

Fuji Super Micro Photoplate HM-G (glass plate)

SPECTRAL SENSITIVITY

Orthochromatic

SAFELIGHT

Use a Fuji Safelight Filter SLF-6 (dark red) with a 20 watt lamp. Handle the plate at a distance of at least 1 meter away from the safelight.

SIZE, THICKNESS, AND PACKING

<table>
<thead>
<tr>
<th>Size</th>
<th>Plate thickness</th>
<th>Packing unit</th>
</tr>
</thead>
<tbody>
<tr>
<td>mm</td>
<td>inch</td>
<td>mm</td>
</tr>
</tbody>
</table>
| 356 x 432     | 14 x 17         | 1.6          | 0.06 | 10
| 356 x 432     | 14 x 17         | 2.3          | 0.09 | 10
| 432 x 432     | 17 x 17         | 1.6          | 0.06 | 10
| 432 x 432     | 17 x 17         | 2.3          | 0.09 | 10
| 508 x 610     | 20 x 24         | 5.0          | 0.19 | 6
| 610 x 813     | 24 x 32         | 5.0          | 0.19 | 6
| 711 x 813     | 28 x 32         | 5.0          | 0.19 | 6

* For inquiries about plate type, size, and thickness, contact our sales personnel.

PROCESSING (DISCH DEVELOPMENT)

<table>
<thead>
<tr>
<th>Step</th>
<th>Chemical</th>
<th>Temperature</th>
<th>Time</th>
<th>Mixing</th>
</tr>
</thead>
<tbody>
<tr>
<td>Develop-ment</td>
<td>LD-735KN Chemical: Water = 2 : 3 (Concentrated liquid developer)</td>
<td>20°C</td>
<td>300 sec.</td>
<td>Continuous</td>
</tr>
<tr>
<td>Stop Bath</td>
<td>Acetic acid solution (3% - 5%) (Dilute Fuji Acetic Acid 50% with 10 - 15 parts of water for use.)</td>
<td>18 - 22°C</td>
<td>10 - 30 sec.</td>
<td>Continuous</td>
</tr>
<tr>
<td>Fixing</td>
<td>LF-505, LF-305 (Concentrated liquid fixer)</td>
<td>18 - 22°C</td>
<td>180 sec.</td>
<td>Continuous</td>
</tr>
<tr>
<td>Washing</td>
<td>Running water (Be sure to use pure water for final wash.)</td>
<td>18 - 22°C</td>
<td>10 min.</td>
<td>——</td>
</tr>
<tr>
<td>Drying</td>
<td>Air drying (Dry in a dust and dirt free environment such as clean bench.)</td>
<td>——</td>
<td>——</td>
<td>——</td>
</tr>
</tbody>
</table>

* For inquiries about developing conditions with automatic processors, contact our sales personnel.
CHARACTERISTIC CURVE

HM-G characteristic curve
Exposure: Xe light source, 10^3 sec., 530 nm filter
Development: LD-735KN, 20°C, 5 min.

EXPOSURE vs. LINE-WIDTH

100 μm line variation
LATENT IMAGE STABILITY

UV TRANSMITTANCE
AFTER PROCESSING